

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 10-282649

(43)Date of publication of application : 23.10.1998

(51)Int.Cl.

G03F 7/004
 G03F 7/022
 G03F 7/038
 G03F 7/039
 G03F 7/039
 H01L 21/027

(21)Application number : 09-149744

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(22)Date of filing : 06.06.1997

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(30)Priority

Priority number : 08166607 Priority date : 07.06.1996 Priority country : JP

08242560 27.08.1996

JP

09 38538 07.02.1997

JP

(54) RESIST COMPOSITION AND ITS PRODUCTION**(57)Abstract:**

PROBLEM TO BE SOLVED: To obtain a resist compsn. which enables highly accurate processing by preparing a resist compsn. consisting of a resist and fine particles comprising aggregation of carbon atoms as the main constituent element mixed in the resist.

SOLUTION: This resist compsn. contains a resist and fine particles comprising aggregation of carbon atoms as the main constituent element mixed in the resist. Intrusion of etching reaction seeds into the film is inhibited and the etching durability of the resist film is enhanced because vacancies among the resists are filled with the fine particles, which increases the density of the resist film, and because the fine particles is composed of aggregation of carbon atoms as the main constituent element having high etching durability. Not only the enhancement of the etching durability, but intrusion of a developer into the film is inhibited and the contrast of the resist pattern is enhanced. As for the aggregation of carbon atoms as the main structural element, a fullerene can be used.

LEGAL STATUS

[Date of request for examination] 18.10.2000

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number] 3515326

[Date of registration] 23.01.2004

[Number of appeal against examiner's decision of
rejection]

[Date of requesting appeal against examiner's
decision of rejection]

[Date of extinction of right]

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